

## AMENDMENT

In response to the Office Action of November 6, 2001, please amend the above-identified application as follows:

**In the Claims:**

Please amend claim 1 as follows:

1.(AMENDED) A coaxial polishing-dressing apparatus comprising:  
[ a polishing platen having an upper surface on which a polishing pad is  
affixed, said polishing platen being rotated in one direction along a  
central axis thereof; ]  
5 a plurality of coaxial polishing-dressing head assemblies each having a  
lower nesting surface opposed to an upper surface of the polishing pad  
on said polishing platen, a nesting means releasably holding a substrate  
to be polished, said coaxial assembly means rotating along a central axis  
thereof and pressing the substrates on a radial portion of said rotating  
10 polishing pad;  
827 annular dressing rings for dressing said polishing pad are positioned  
coaxially encircling each nested substrate, said annular dressing  
rings are removably attached to said lower surface of a plurality of  
substrate nesting support heads, and  
15 compressing means for applying a polishing and dressing pressure to said  
coaxial polishing-dressing head assemblies, whereby the substrate  
polishing-dressing head assemblies are pressed against the upper surface  
of the polishing pad.